

Title (en)

METHOD AND APPARATUS FOR COATING A SUBSTRATE IN A VACUUM

Title (de)

VERFAHREN UND VORRICHTUNG ZUM BESCHICHTEN EINES SUBSTRATES IM VAKUUM

Title (fr)

PROCEDE ET APPAREIL DESTINE AU DEPOT SOUS VIDE D'UN REVETEMENT SUR UN SUBSTRAT

Publication

EP 1246951 A1 20021009 (EN)

Application

EP 00975328 A 20001020

Priority

- US 0029099 W 20001020
- US 16109499 P 19991022

Abstract (en)

[origin: WO0131081A1] A method and apparatus for coating a substrate with a deposition material in a vacuum wherein a material source having a substantially longitudinal deposition emission component is used to create a substantially longitudinal material deposition emission plume which coats a surface of the substrate without increasing the throw distance between the substrate and the material source.

IPC 1-7

C23C 14/24; **C23C 14/12**

IPC 8 full level

C23C 14/12 (2006.01); **C23C 14/24** (2006.01)

CPC (source: EP KR)

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